

## PATENT ABSTRACTS OF JAPAN

(11)Publication number : 06-241992

(43)Date of publication of application : 02.09.1994

(51)Int.Cl.

G01N 21/35

(21)Application number : 05-055141

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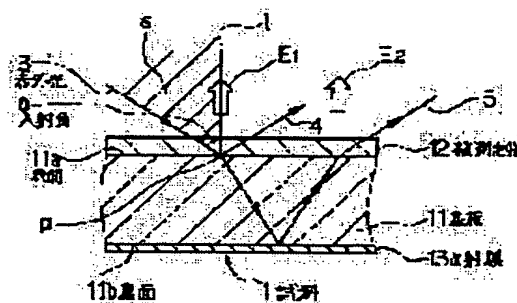
(22)Date of filing : 19.02.1993

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SAOTOME NOBUYUKI**(54) METHOD FOR MEASURING INFRARED REFLECTION SPECTRUM AND ITS SAMPLE**

(57)Abstract:

**PURPOSE:** To provide a method for measuring infrared reflection spectrum which can detect an extremely thin film formed on the surface of a substrate for semi-transmitting infrared light and its sample.

**CONSTITUTION:** A rear surface 11b of a sample 1 where an object 12 to be measured in thin-film state is formed on a surface 11a of a substrate 11 for transmitting infrared light is polished to mirror-surface state. Then, a reflection film 13 for reflecting infrared light is stuck to the rear surface 11b which is polished to mirror surface. Then, infrared light 3 which is subjected to P polarization is applied to the sample 1 from the side of the object 12 to be measured. Then, the spectra of the infrared rays 4 and 5 which are reflected from the sample 1 are measured. Also, the surface 11a of the substrate 11 is in mirror-surface state.

**LEGAL STATUS**

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against

examiner's decision of rejection]

[Date of extinction of right]

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